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(54) Title (EN): PRODUCTION METHOD FOR PATTERN-WORKED POROUS MOLDING OR NONWOVEN FABRIC, AND ELECTRIC CIRCUIT COMPONENTS

(54) Title (FR): PROCEDE DE PRODUCTION DE MOULAGE POREUX A MOTIFS TRAVAILLES OU DE TISSU NON TISSE ET COMPOSANTS DE CIRCUIT ELECTRIQUE

(54) Title (JA): パターン加工した多孔質成形体または不織布の製造方法、及び電気回路部品

(57) Abstract:

(EN): A production method for a porous molding in which complicated and fine penetrated portions and recesses are pattern-worked. A pattern-worked porous molding or non-woven fabric in which a plated layer is selectively formed on the surfaces of penetrated portions and recesses. A mask having pattern-form penetrated portions is disposed on at least one surface of a porous molding or non-woven fabric, and fluid or fluid containing abrasive grains is sprayed over the mask to form penetrated portions or recesses or the both of them, to which the opening shape of the mask's penetrated portion is transferred, on the porous molding or non-woven fabric. A porous molding or non-woven fabric and an electric circuit components or the like in which a plated layer is selectively formed on the surfaces of penetrated portions or recesses or the both of them.

(FR): L'invention concerne un procédé de production d'un moulage poreux comprenant des parties compliquées et percées finement et des évidements à motifs travaillés. L'invention concerne également un moulage poreux à motifs travaillés ou un tissu

non tissé sur lequel une couche plaquée est sélectivement formée sur les surfaces des parties percées et des évidements. Un masque comprenant des parties percées en forme de motifs est disposé sur au moins une surface de moulage poreux ou de tissu non tissé, et un fluide ou des grains abrasifs contenant un fluide est pulvérisé sur ledit masque afin de former des parties percées ou des évidements ou les deux. La forme d'ouverture de la partie percée du masque est transférée sur le moulage poreux ou le tissu non tissé. L'invention concerne également un moulage poreux ou un tissu non tissé et des composants de circuit électrique ou analogues dans lesquels une couche plaquée est sélectivement formée sur les surfaces des parties percées ou des évidements ou les deux.

(JA): 本発明の課題は、複雑かつ微細な貫通部や凹部などをパターン加工した多孔質素材の製造方法を提供すること。貫通部や凹部の表面に選択的にめっき層が形成されているパターン加工した多孔質成形体または不織布を提供することである。本発明は、多孔質成形体または不織布の少なくとも片面に、パターン状の貫通部を有するマスクを配置し、該マスクの上から、流体または砥粒を含有する流体を吹き付けて、多孔質成形体または不織布に、マスクの貫通部の開口形状が転写された貫通部、凹部もしくはこれらの両方を形成する。該貫通部、凹部もしくはこれらの両方の表面に選択的にめっき層が形成されている多孔質成形体または不織布、電気回路部品等である。

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